ABSTRACT

A substrate for an information recording medium, which has high heat resistance and high acid resistance and is formed of a glass having a glass transition temperature (Tg) of 600°C or higher and having an etching rate of 0.1 μm/minute or less with regard to a hydrosilicofluoric acid aqueous solution that is maintained at a temperature of 45°C and has a hydrosilicofluoric acid concentration of 1.72 % by weight, and an information recording medium having an information recording layer formed on the above substrate.